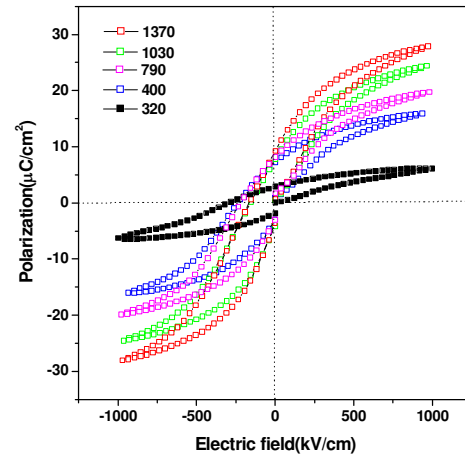


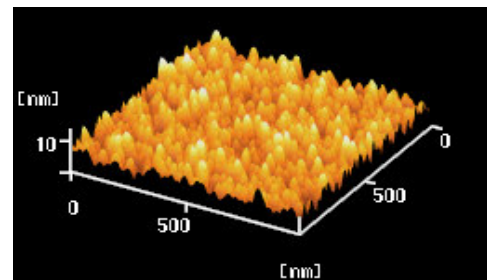
ATS-PVD Series UHV Sputter System with 4x3" Guns



P-E hysteresis of PZT thin films



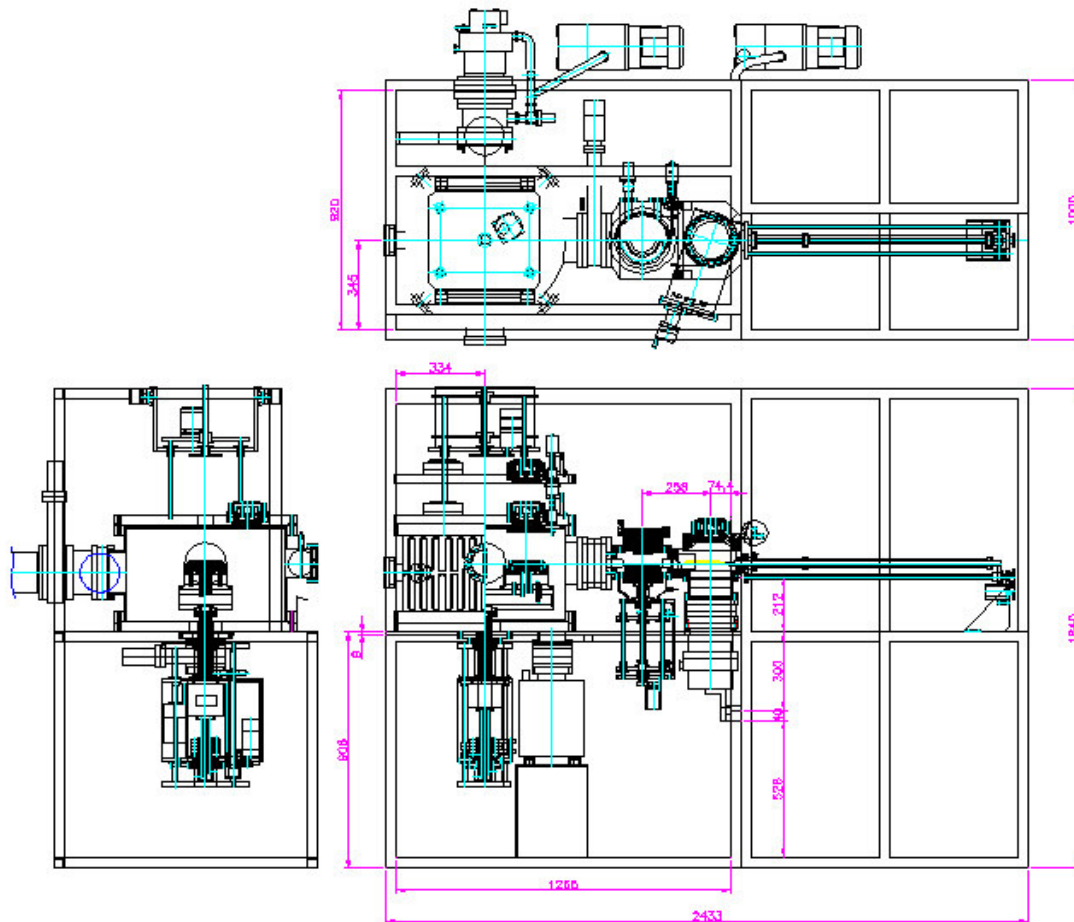
AFM analysis of PZT layer



Special Features

- ◆ Ultra-high-vacuum sputter system for R&D and small scale production (base pressure: 6×10^{-9} Torr)
- ◆ Pumping system equipped with ion and turbo molecular pumps
- ◆ Predeposition process of oxides or metals in load-lock chamber
- ◆ Automatic mask loading system
- ◆ Permanent magnetic system installed in main chamber
- ◆ Applications
 - Ferromagnetic materials deposition
 - Oxides deposition
 - Metals deposition
- ◆ Wafer capacity
 - $4 \times 3''$ ($4 \times 4''$)
- ◆ Average throughput
 - Up to 20,000 wafers per year
- ◆ Dimension
 - 1575L X 1720H X 930W (mm³)
- ◆ Others
 - Power : AC 600W (13.56MHz)
 - Gas : Ar / O₂
 - Pump : rotary(980l/min) & turbo(1000l/s) ionization(500l/s)

◇ Layout



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